

PROCEEDINGS OF SPIE

Advances in Metrology for X-Ray and EUV Optics X

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**23 August 2023
San Diego, California, United States**

Sponsored and Published by
SPIE

Volume 12695

Proceedings of SPIE 0277-786X, V. 12695

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

Advances in Metrology for X-Ray and EUV Optics X, edited by Lahsen Assoufid,
Haruhiko Ohashi, Frank Siewert, Proc. of SPIE Vol. 12695, 1269501
© 2023 SPIE · 0277-786X · doi: 10.1117/12.3012884

Proc. of SPIE Vol. 12695 1269501-1

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Please use the following format to cite material from these proceedings:
Author(s), "Title of Paper," in *Advances in Metrology for X-Ray and EUV Optics X*, edited by Lahsen Assoufid, Haruhiko Ohashi, Frank Siewert, Proc. of SPIE 12695, Seven-digit Article CID Number (DD/MM/YYYY); (DOI URL).

ISSN: 0277-786X
ISSN: 1996-756X (electronic)

ISBN: 9781510666047
ISBN: 9781510666054 (electronic)

Published by
SPIE
P.O. Box 10, Bellingham, Washington 98227-0010 USA
Telephone +1 360 676 3290 (Pacific Time)
SPIE.org
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